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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/668,021	09/22/2003	Michael J. Berman	03-0915	1398
24319	7590 01/19/2005		EXAMINER	
LSI LOGIC CORPORATION			RACHUBA, MAURINA T	
1621 BARBI MS: D-106	ER LANE		ART UNIT	PAPER NUMBER
MILPITAS,	CA 95035		3723	
			DATE MAILED: 01/19/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	
	10/668,021	BERMAN ET AL.	
Office Action Summary	Examiner	Art Unit	•
	M Rachuba	3723	
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the (orrespondence address	
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period of Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from to become ABANDONE	mely filed ys will be considered timely. the mailing date of this communication. ED (35 U.S.C. § 133).	
Status			
1) ☐ Responsive to communication(s) filed on <u>03 N</u> 2a) ☐ This action is FINAL . 2b) ☐ This 3) ☐ Since this application is in condition for allowal closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro		
Disposition of Claims		•	
4) Claim(s) 1-9,19 and 20 is/are pending in the appear 4a) Of the above claim(s) is/are withdraw 5) Claim(s) is/are allowed. 6) Claim(s) 1-9,19 and 20 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or are subjected to by the Examine 10) The drawing(s) filed on 22 September 2003 is/as	wn from consideration. or election requirement. er.	cted to by the Examiner.	
Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	drawing(s) be held in abeyance. Se tion is required if the drawing(s) is ob	e 37 CFR 1.85(a). ejected to. See 37 CFR 1.121(d).	
Priority under 35 U.S.C. § 119			
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list 	s have been received. s have been received in Applicat rity documents have been receiv u (PCT Rule 17.2(a)).	ion No ed in this National Stage	
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal R 6) Other:	· ·	

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DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-9 and 19-20 are finally rejected under 35 U.S.C. 102(a) or (e) as being clearly anticipated by Lin 6,477,447. Note especially figure 6 and its description.

 Regarding claims 1-9, 19 and 20, '447 discloses the claimed invention used to determine the pressure uniformity of a wafer against a polishing pad, or other pressure components ("In addition, the pressure components applied in the embodiment of the present invention refer to, but not limited to, mechanical CMP pressure related components including a wafer carrier, a polishing pad, and mechanical arm members of a CMP machine.", column 3, lines 37-42). It is inherent that a conditioner for a polishing pad exerts pressure on the pad, and therefore qualifies as a pressure related component. As evidence of inherency, the examiner cites Berman, 6,722,948, which discloses that a conditioning tool to condition a wafer polishing pad is a pressure related component, and that it is known to measure the uniformity of pressure across the conditioning component.

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Response to Arguments

- 3. Applicant's arguments filed 03 November 2004 have been fully considered but they are not persuasive. Applicant argues that the rejections are based on impermissible broadening of the phrase "pressure related components" as used by Lin. Applicant argues that the pressure related components disclosed by Lin deal only with the wafer polishing subsystem, and not every pressure related component of a chemical mechanical polishing system. The examiner disagrees. Lin clearly states that the pressure components are **not** limited to what applicant calls the wafer polishing subsystem, but any pressure related component used in a chemical mechanical polishing system. Applicant's conditioner, as broadly claimed, is a pressure related component used in a chemical mechanical polishing system. Applicant's argument that his claimed invention is patentable over Lin because Lin discloses the broad concept of pressure related components, and but not all the types of pressure related components used with a chemical mechanical polishing system is not convincing. MPEP 2123 states: "The use of patents as references is not limited to what the patentees describe as their own inventions or to the problems with which they are concerned. They are part of the literature of the art, relevant for all they contain." In re Heck, 699 F.2d 1331, 1332-33, 216 USPQ 1038, 1039 (Fed. Cir. 1983) (quoting In re Lemelson, 397 F.2d 1006, 1009, 158 USPQ 275, 277 (CCPA 1968)).
- 4. In response to applicant's argument that Lin does not disclose the claimed method used with a conditioner, a recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in

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order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim. In a claim drawn to a process of making, the intended use must result in a manipulative difference as compared to the prior art. See *In re Casey*, 152 USPQ 235 (CCPA 1967) and *In re Otto*, 136 USPQ 458, 459 (CCPA 1963).

5. Regarding applicant's arguments concerning Berman, the examiner cannot agree. Berman does prove that a conditioner is inherently a pressure related component in a chemical mechanical polishing system. Applicant has not provided evidence that one of ordinary skill would not consider a conditioner a pressure related component in a chemical mechanical polishing system.

Conclusion

6. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

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7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to M Rachuba whose telephone number is **(571) 272-4493**. The examiner can normally be reached on Monday-Thursday from 8:30 AM to 3:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph Hail, can be reached on (571) 272-4485. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

M. Rachuba
Primary Patent Examiner